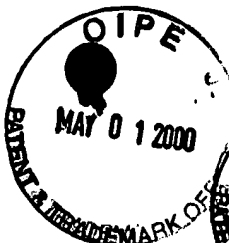


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Attorney Docket No.: NEKW14.868

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor : KAICHIRO NAKANO, ET AL.
Serial No. : 09/036,219
Filed : March 6, 1998
Title : **CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE
LIGHT LESS THAN 248 NANOMETER WAVELENGTH
AND PROCESS OF FORMING MASK**
Examiner : J. Chu
Group Art Unit : 1752

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May 1, 2000

Assistant Commissioner for Patents
Washington, D.C. 20231

SUB-POWER OF ATTORNEY

S I R :

I, Samson Helfgott, attorney of record herein, do hereby grant a sub-power of attorney to Linda S. Chan, Reg. No. 42,400; Jacqueline M. Steady, Reg. No. 44,354; and, Harris A. Wolin, Reg. No. 39,432 to act and sign in my behalf in the above-referenced application.

Respectfully submitted,

[Signature]

Samson Helfgott
Reg. No. 28,072

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